AMENDMENT TO THE CLAIMS:

This listing of claims will replace all prior versions of claims in the application:

LISTING OF CLAIMS:

1-16. (CANCELLED)

17. (CURRENTLY AMENDED) A method of making comprising the steps of:

making a read head including the steps of:

forming a read sensor;

forming first and second lead layers with the first and second lead layers connected to the read sensor;

forming nonmagnetic insulative first and second read gap layers with the read sensor and the first and second lead layers located between the first and second read gap layers;

forming ferromagnetic first and second shield layers with the first and second read gap layers located between the first and second shield layers and the first read gap layer having a resistance R_{G1} between the first shield layer and one of the first and second lead layers and the second read gap having a resistance R_{G2} between the second shield layer and said one of the first and second lead layers;

forming a connection via a plurality of resistors between a first node and each of the first and second shield layers wherein the plurality of resistors includes at least first and second resistors R_{G1} and R_{G2} R_{S1} and R_{S2} the first node is connected to said one of the first and second lead layers and a second node is located between the first and second resistors R_{S1} and R_{S2} and

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connecting first and second inputs of an operational amplifier to the first and second nodes respectively so as to be across the first resistor R_{S1} and connecting an output of the operational amplifier to the first second node for maintaining the first and second nodes at a common voltage potential.

- 18. (ORIGINAL) A method of making as claimed in claim 17 including making the sensor and the first and second resistances R_{s1} and R_{s2} coplanar.
- 19. (CURRENTLY AMENDED) A method of making as claimed in claim 18 wherein the step of making the sensor and the first and second resistances R_{s1} and R_{s2} coplanar includes the steps of:

simultaneously depositing a single layer of material for the sensor and the first and second resistances R_{S1} and R_{S2} and

simultaneously patterning said single layer of material to form the sensor and the first and second resistances R_{S1} and R_{S2} .

- 20. (ORIGINAL) A method of making as claimed in claim 17 including: connecting a first side of a test instrument for enabling a determination of resistance to the first node and connecting a second side of the test instrument to at least one of the first and second shield layers.
- 21. (ORIGINAL) A method of making as claimed in claim 20 including: shorting the first and second shield layers together; and connecting the second side of the test instrument to each of the first and second shield layers.
- 22. (ORIGINAL) A method of making as claimed in claim 21 including making the sensor and the first and second resistances R_{S1} and R_{S2} coplanar.

23. (ORIGINAL) A method of making as claimed in claim 22 wherein a the step of making the sensor and the first and second resistances $R_{\rm S1}$ and $R_{\rm S2}$ coplanar includes the steps of:

simultaneously depositing a single layer of material for the sensor and the first and second resistances R_{S1} and R_{S2} and

simultaneously patterning said single layer of material to form the sensor and the first and second resistances $R_{\rm S1}$ and $R_{\rm S2}$.

24. (ORIGINAL) A method of making as claimed in claim 23 further comprising the steps of:

making a write head including the steps of:

forming ferromagnetic first and second pole piece layers with a yoke portion between a pole tip portion and a back gap portion;

forming a nonmagnetic write gap layer between the pole tip portions of the first and second pole piece layers;

forming an insulation stack with at least one coil layer embedded therein located between the yoke portions of the first and second pole piece layers; and connecting the first and second pole piece layers at their back gap portions.

- 25. (ORIGINAL) A method of making as claimed in claim 24 wherein the second shield layer and the first pole piece layer are formed as a common layer.
- 26. (ORIGINAL) A method of making as claimed in claim 24 wherein the second shield layer and the first pole piece layer are formed as separate layers; and forming a nonmagnetic insulative isolation layer between the second shield layer and the first pole piece layer.
 - 27. (ORIGINAL) A method of making as claimed in claim 17 including:

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the second resistor R_{S2} further being connected between the second node and the second shield layer; and

connecting a third resistor R₈₃ between the second node and the first shield layer.

- (ORIGINAL) A method of making as claimed in claim 27 including 28. making the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3} coplanar.
- (ORIGINAL) A method of making as claimed in claim 28 wherein the 29. step of making the sensor and the first, second and third resistances R_{S1} , R_{S2} and R_{S3} includes the steps of:

simultaneously depositing a single layer of material for the sensor and the first, second and third resistances Rs1 Rs2 and Rs3 and

simultaneously patterning said single layer of material to form the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3}.

- (ORIGINAL) A method of making as claimed in claim 27 including: 30. connecting a first side of a test instrument for enabling a determination of resistance to the first node and connecting a second side of the test instrument to the first shield layer.
- (ORIGINAL) A method of making as claimed in claim 30 including making the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3} coplanar.
- (ORIGINAL) A method of making as claimed in claim 31 wherein the 32. step of making the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3} includes the steps of:

simultaneously depositing a single layer of material for the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3} and

simultaneously patterning said single layer of material to form the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3} .

- 33. (ORIGINAL) A method of making as claimed in claim 32 wherein the second shield layer and the first pole piece layer are formed as a common layer.
- 34. (ORIGINAL) A method of making as claimed in claim 32 wherein the second shield layer and the first pole piece layer are formed as separate layers; and forming a nonmagnetic insulative isolation layer between the second shield layer and the first pole piece layer.
 - 35. (ORIGINAL) A method of making as claimed in claim 27 including:

connecting a first side of a test instrument for enabling a determination of resistance to the first node and connecting a second side of the test instrument to the second shield layer.

- 36. (ORIGINAL) A method of making as claimed in claim 35 including making the sensor and the first, second and third resistances R_{S1} R_{S2} and R_{S3} coplanar.
- 37. (CURENTLY AMENDED) A method of making as claimed in claim 36 wherein the step of making the sensor and the first, second and third resistances $R_{\rm S1}$ $R_{\rm S2}$ and $R_{\rm S3}$ includes the steps of:

simultaneously depositing a single layer of material for the sensor and the first, second and third resistances R_{s1} R_{s2} and R_{s3} and

simultaneously patterning said single layer of material to form the sensor and the first, second and third resistances $R_{\rm S1}$ $R_{\rm S2}$ and $R_{\rm S3}$

- 38. (ORIGINAL) A method of as claimed in claim 37 wherein the second shield layer and the first pole piece layer are formed as a common layer.
- 39. (ORIGINAL) A method of making as claimed in claim 37 wherein the second shield layer and the first pole piece layer are formed as separate layers; and forming a nonmagnetic insulative isolation layer between the second shield layer and the first pole piece layer.